

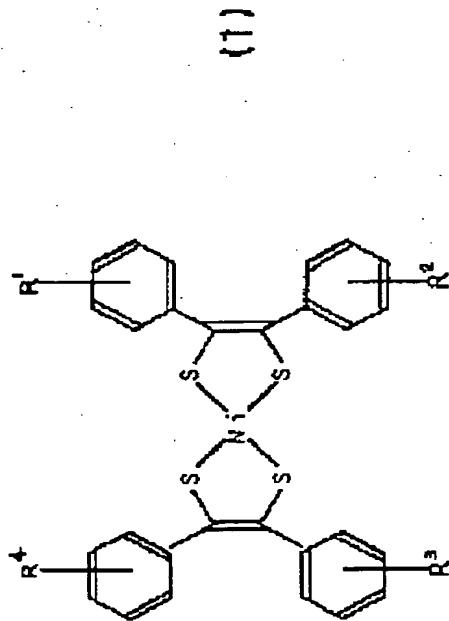
99-148685/13 A89 E23 G06 L03 **MITR 97.06.23** A(4-F1A, 12-L3D) E(5-L2C) G(6-A3, 6-A11, 6-F4, 6-
MTSUBISHI RAYON CO LTD *JP 11012425-A F5) L(3-G5)

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Optical filter for plasma display.

C99-044043

Optical filter(I) for plasma display comprising (A) and (B) is claimed.
(A): acrylic resin film(s) or sheet(s) (B): nickel complex(es) of
formula (I):



Also claimed, are:
(1) an optical filter(II) for plasma display comprising (I) and one of
electrically conductive layer, antistatic layer or reflection insulating
layer; and
(2) an optical filter(III) for plasma display comprising (I) or (II) and
glass plate or plastic plate(s) to support (I) or (II).

ADVANTAGE

(I) absorbs near infrared ray selectively. Using (I), (II) or (III),
clear image of plasma display is obtained, errors of electrical and
electronic instruments can be avoided by using (I), (II) or (III).

EMBODIMENT

(A) is film(s) or sheet(s) of methyl methacrylate homopolymer
plate or methyl methacrylate copolymer. Polymer(s) corresponding
to (A) and (B) are blended to become (B) content in (I) to 0.07-1.07
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g/m^2 , the mixt. moulded to film(s) or sheet(s) to obtain (I). One of electrically conductive layer(e.g. silver thin layer and/or ITO thin layer), antistatic layer(e.g. surface active agent layer) or reflection insulating layer(e.g. silica layer, titania layer etc) is formed on (I) surface to obtain (II). (I) or (II) is formed on glass or plastic plate(s) to obtain (III).

EMBODIMENT

(B1), cpd. R1-R4=p-methoxy in formula (1), was added to Acrypt V/H(RTM), the mixt. was moulded to film containing (B1) 0.39 g/m^2 to obtain (I). (I) showed transmittance 15 % at 920 nm, 68 % at 450-680 nm region.
(KR)

(app129DwgNo.0/0)

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